

(19) World Intellectual Property Organization
International Bureau



G00002

(43) International Publication Date
14 March 2002 (14.03.2002)

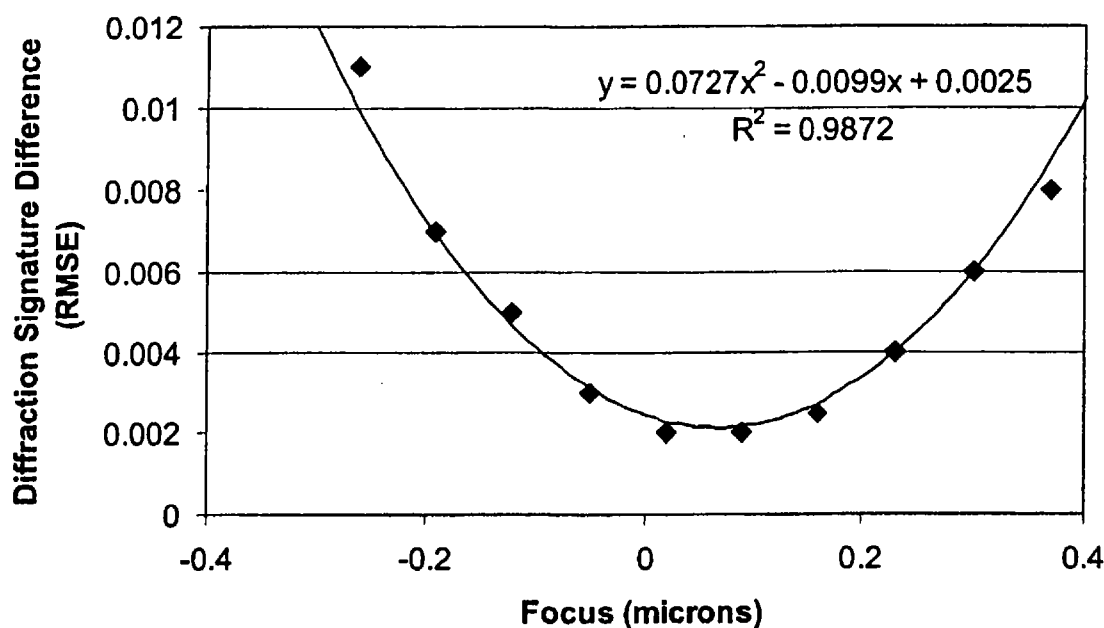
PCT

(10) International Publication Number
WO 02/21075 A1

- (51) International Patent Classification⁷: **G01B 9/00**
- (21) International Application Number: PCT/US01/27657
- (22) International Filing Date:
5 September 2001 (05.09.2001)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
60/230,491 6 September 2000 (06.09.2000) US
09/946,104 4 September 2001 (04.09.2001) US
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- (81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW.
- (84) Designated States (regional): ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).
- Published:
with international search report
before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments

[Continued on next page]

(54) Title: DETERMINATION OF CENTER OF FOCUS BY DIFFRACTION SIGNATURE ANALYSIS



(57) Abstract: The present invention provides methods for determination in lithographic wafer (10) by diffraction signature difference analysis utilizing a plurality of diffraction gratings (20).

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